

	Hits	Search Text	DBs
26	136	(develop\$5 same (displac\$4 or remov\$4 or eliminat\$4) same (surfactant or (surface near9 active) or defect or (hydrophilic\$4 near9 group))) and ((resist or photoresist) same (expos\$4 or illuminant\$4 or irradiat\$4) same develop\$4) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)) and ((remov\$4 or displac\$4 or eliminat\$4) same (surfactant) same (develop\$4 same (supply or apply\$4 or spray)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
27	50	(develop\$5 same (displac\$4 or remov\$4 or eliminat\$4) same (surfactant or (surface near9 active) or defect or (hydrophilic\$4 near9 group))) and ((resist or photoresist) same (expos\$4 or illuminant\$4 or irradiat\$4) same develop\$4) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)) and ((remov\$4 or displac\$4 or eliminat\$4) same (surfactant) same (develop\$4 same (supply or apply\$4 or spray)) same (substrate or wafer) same (resist or photoresist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	113	(develop\$5 near16 (supply or nozzle or spray or appli\$5) same (surfactant or (surface near9 active) or defect or (hydrophilic\$4 near9 group))) and ((resist or photoresist) same (expos\$4 or illuminant\$4 or irradiat\$4) same develop\$4) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)) and ((remov\$4 or displac\$4 or eliminat\$4) same (surfactant))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB